

Amendments to the Specification

Please replace the paragraph beginning on page 12, line 9, with the following rewritten paragraph:

A' In the manufacturing method, as shown in FIG. 3A and FIG. 3B, an insulating layer 2 made of an insulating material such as alumina (Al_2O_3) or silicon dioxide (SiO_2) whose thickness is 1 to 20 μm , for example, is formed through sputtering, for example, on a substrate 1 made of a ceramic material such as aluminum oxide and titanium carbide (Al_2O_3 -TiC). On the insulating layer 2 a bottom shield layer 3 made of a magnetic material and having a thickness of 0.1 to 5 μm , for example, is formed for making a read head. The bottom shield layer 3 is made of a magnetic material such as FeAlSiFeAlSi, NiFe, CoFe, CoFeNi, FeN, FeZrN, FeTaN, CoZrNb, or CoZrTa. The bottom shield layer 3 is formed through sputtering or plating.